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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION N
09/696,232	10/26/2000	Mitsuru Ishikawa	07553.0017	5127
	7590 09/16/2004		EXAMINER	
FINNEGAN, HENDERSON, FARABOW, GARRETT & DUNNER LLP 1300 I STREET, NW			OLSEN, ALLAN W	
			ART UNIT	PAPER NUMBER
WASHINGTON, DC 20005			1763	
			DATE MAIL ED: 00/16/2004	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
Office Action Summary	09/696,232	ISHIKAWA ET AL.				
Office Action Summary	Examiner	Art Unit				
The MAILING DATE of this area in the	Allan Olsen	1763				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply						
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). - Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b). Status						
1) Responsive to communication(s) filed on <u>06 Ju</u>	<u>uly 2004</u> .					
2a)⊠ This action is FINAL . 2b)□ This	s action is non-final.					
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213. Disposition of Claims						
4)⊠ Claim(s) <u>1-5,14 and 17</u> is/are pending in the application.						
4a) Of the above claim(s) is/are withdrawn from consideration.						
5) Claim(s) is/are allowed.						
6)⊠ Claim(s) <u>1-5,14 and 17</u> is/are rejected.						
7) Claim(s) is/are objected to.						
8) Claim(s) are subject to restriction and/or election requirement. Application Papers						
9) The specification is objected to by the Examiner.						
10)⊠ The drawing(s) filed on <u>18 March 2003</u> is/are: a)⊠ accepted or b)⊡ objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
11)☐ The proposed drawing correction filed on is: a)☐ approved b)☐ disapproved by the Examiner.						
If approved, corrected drawings are required in reply to this Office action.						
12) The oath or declaration is objected to by the Examiner.						
Priority under 35 U.S.C. §§ 119 and 120						
13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).						
a)⊠ All b)☐ Some * c)⊡ None of:						
1. Certified copies of the priority documents have been received.						
2. Certified copies of the priority documents have been received in Application No						
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 						
14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).						
a) ☐ The translation of the foreign language provisional application has been received. 15)☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.						
Attachment(s)						
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449) Paper No(s)	5) Notice of Informal Pa	(PTO-413) Paper No(s). <u>20040420</u> . atent Application (PTO-152)				

DETAILED ACTION

Claim Rejections - 35 USC § 112

The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

Claims 1-5 and 14 are rejected under 35 U.S.C. 112, first paragraph, because the specification, while enabling the use an etching gas mixture comprising CF4 and N2 or C₄F₈and N₂ to etch both layers of a target film that comprises a top layer of an organic film that contains Si and bottom SiO₂ layer, does not reasonably provide enablement for a process that uses these same etchant wherein the etching proceeds through the top layer of the target film but stops upon reaching the bottom SiO₂. The specification does not enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to use the invention commensurate in scope with these claims. The specification repeatedly states the object of the invention is to etch the target film. The specification defines the target film as having an upper Sicontaining organic layer and a bottom SiO2 layer. The examiner fails to find an enabling disclosure for an etching process that uses a SiO2 etchant and in which the etching ceases when a SiO2 layer is reached. The examiner notes that the claim language appears to be taken from page 7, lines 6-8 of the specification which parallels the language used on page 10 of the specification when describing a method wherein the bottom layer is SiN.

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Claim 17 is rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the enablement requirement. The claims contains subject matter which was not described in the specification in such a way as to enable one skilled in the art to which it pertains, or with which it is most nearly connected, to make and/or use the invention. The claim requires that "a temperature of a bottom portion of at least one of the contact holes is maintained at about –20° C, a temperature of an opening portion of at least one of the contact holes is maintained at about 30° C, and a temperature of a sidewall portion of at least one of the contact holes is maintained at about 50° C", however, the specification provides no guidance as to how on is to obtain such a temperature profile.

Claim 17 is rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the written description requirement. The claims contains subject matter which was not described in the specification in such a way as to reasonably convey to one skilled in the relevant art that the inventors, at the time the application was filed, had possession of the claimed invention.

Claim 17 recites "a temperature of a bottom portion of at least one of the contact holes is maintained at about –20° C, a temperature of an opening portion of at least one of the contact holes is maintained at about 30° C, and a temperature of a sidewall portion of at least one of the contact holes is maintained at about 50° C" (emphasis added). This is in contrast to the disclosure of the first paragraph on page 8 of the specification, which reads (with emphasis added):

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"First, the wafer W is placed on the lower electrode 106, the temperature of which has been adjusted to a specific level in advance, and the temperature of the wafer W is sustained within a range of approximately –20° C ~ 50° C in correspondence to the particulars of the processing. For instance, the temperature at the bottom of the contact holes is sustained at approximately –20° C, the temperature at the openings is sustained at approximately 30° C and the temperature at the sidewalls is sustained at approximately 50°C."

The specification indicates that the temperature profile of –20° C at the bottom, 30° C at the opening and 50° C at the sidewalls is the temperature profile of each individual contact hole whereas the claim supports an across wafer temperature gradient that is not supported by the specification.

Response to Arguments

Applicant's arguments have been considered but are moot in view of the new grounds of rejection.

Conclusion

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any

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extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Allan Olsen whose telephone number is 571-272-1441. The examiner can normally be reached on M-F 1-5.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Greg Mills can be reached on 571-272-1439. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Allan Olsen
Primary Examiner
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